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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : Box Non-Fee Amendment

Satoshi Watanabe et al.

Serial No.: 09/401,490

Filed: September 22, 1999

Group Art Unit: 1765

Examiner: V. Perez-Ramos

For: RESIST COMPOSITION AND PATTERNING METHOD

AMENDMENT and RESPONSE

Assistant Commissioner of Patents  
Washington, DC 20231

Sir:

In response to the Office Action mailed July 5, 2001, please amend the above-application as follows and consider the remarks.

IN THE CLAIMS

Please add the following claims:

~~--5.~~ The resist composition of claim 1 further comprising a base polymer.

6. A chemically amplified positive working resist composition comprising:  
a base resin of an alkali-insoluble or scarcely soluble resin having acidic functional groups protected with acid-labile groups wherein the resin becomes alkali soluble when the acid-labile groups are eliminated;  
a photo-acid generator capable of generating acid upon exposure to deep UV, X-rays or electron beams; and  
a fluorochemical surfactant functioning to reduce the contact angle at the interface between the surface of the resist composition coated onto a substrate and water or an aqueous base developer